

Descrizione

Application	Etches Al, Cr, Cu, Ni, GaAs. Surface oxidizes Si, Ta/TaN. No attack on Au, Si ₃ N ₄ , SiO ₂ , Ti, and W surfaces. For use at room temperature or elevated temperature. Etches cleanly, eliminating need for an intermediate rinse. Etching temperature varies with regard to film thickness. Etch times range from 15 to 60 seconds at room temperature. Note, chromium etchants should be handled in a well ventilated hood.
Features and Benefits	Designed for precise, clean etching of chromium and chromium oxide films. Compatible with both positive and negative photoresists. Filtered to 0.2 micron to remove particulates.
Packaging	500 mL in poly btl
General description	Ceric ammonium nitrate-based etchant. Etch rate of 40 Å/sec @ room temp. Etches cleanly with only a deionized water rinse needed.

Proprieta'

grade	standard
composition	volatiles, 85%
color	orange
bp	100 °C/1 atm
density	1.16 g/mL at 25 °C

Sicurezza

Hazard Codes	O,C
Risk Statements	8-34
Safety Statements	17-26-36/37/39-45
RIDADR	UN 3093 8/PG 2
WGK Germany	3